

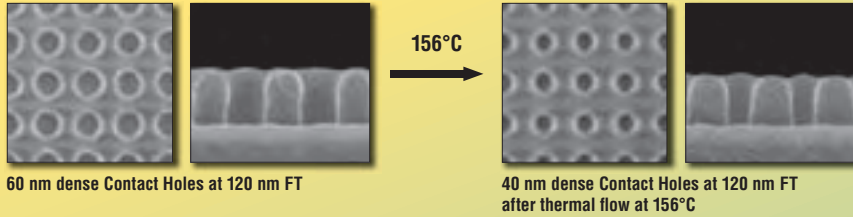
Performance

Litho Extensions

Thermal Flow Performance

EPIC™ 2390 Photoresist

Contact Hole Performance – 20 nm flow amount at 156°C/60sec.

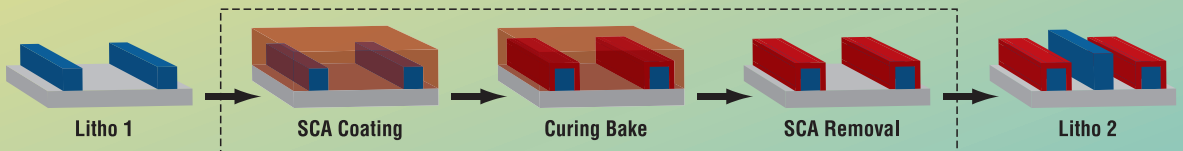


- Excellent contact hole circularity
- 40 nm contact hole resolution with thermal flow

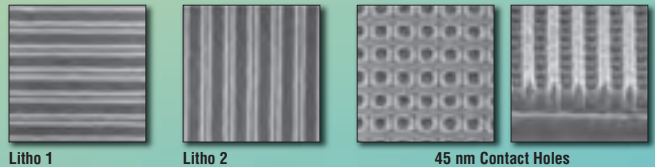
Pattern Freezing Technology for Double Patterning

SC™ 1000 Surface Curing Agent

Double Patterning Using Surface Curing Agent (SCA)

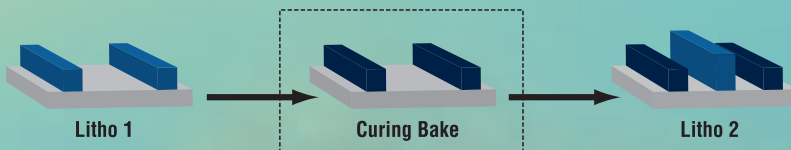


- Pattern curing by three-step chemical and thermal process
- SCA can be used for most POR resists ⇒ No compromise in resolution



EPIC 3000 Series Photoresist

Double Patterning Using Thermally Curable Resist (TCR)



- Pattern curing by one-step thermal process ⇒ Most simple and cost-effective solution
- Special resist formulations with curing capability without compromising resolution

